

ABSTRACT

In general, in one aspect, the invention features a method for determining the location of an alignment mark on a stage including measuring a location, x_1 , of a stage along a first measurement axis using an interferometer, measuring a location, x_2 , of the stage along a second measurement axis substantially parallel to the first measurement axis, and determining a location of the alignment mark along a third axis substantially parallel to the first measurement axis based on x_1 , x_2 , and a correction term, ψ_3 , calculated from predetermined information including information characterizing imperfections in the interferometer.